Application No.: 10/692,588

Docket No.: JCLA10198

<u>AMENDMENT</u>

In The Claims:

Claim 1. (currently amended) An evaporation method, comprising:

providing a substrate, wherein the substrate is rotating along an axis at the center of the substrate and perpendicular to the a plane of the top surface of the substrate;

defining a circular trace on the plane of the top surface of the substrate by using the center of the substrate as the center of the circular trace;

providing a heater right under a point on the circular trace, wherein there is a line on the plane of the substrate as a tangent to the point on the circular trace;

providing a source supplying device, wherein the source supplying device supplies a metal wire as an evaporation source along a source supplying direction to a source evaporation point on the heater along a supplying direction and there is a vector from the source supplying device to the heater along the supplying direction;

adjusting the <u>source</u> supplying direction of the source supplying device so that a projection of the <u>vector</u> <u>source</u> supplying <u>direction</u> on the plane of the substrate <u>is-parallel</u> to <u>overlaps</u> with the <u>line</u> tangent of the circular trace at the point on the circular trace; and

heating the evaporation source by the heater for evaporation.

Claim 2. (original) The evaporation method of claim 1, further comprising disposing a shelter between the source supplying device and the substrate for defining an evaporation region.

Application No.: 10/692,588

Docket No.: JCLA10198

Claim 3. (original) The evaporation method of claim 2, wherein a radius of the evaporation region is substantially similar to that of the circular trace.

Claim 4. (original) The evaporation method of claim 1, wherein a rotational direction of the substrate is clockwise.

Claim 5. (original) The evaporation method of claim 1, wherein a rotational direction of the substrate is counterclockwise.

Claim 6. (original) The evaporation method of claim 1, wherein the evaporation source is aluminum or silver.

Claim 7. (currently amended) An evaporation apparatus for depositing a film on a substrate, the evaporation apparatus comprising:

a rotator driving the substrate to be rotating along an axis at the center of the substrate to define a circular trace on a plane of the top surface of the substrate by using the center of the substrate as the center of the circular trace;

a heater, disposed right under a point on the circular trace, wherein there is a line on the plane of the substrate as a tangent to the point on the circular trace the heater has a source evaporation point thereon; and

a source supplying device, disposed over the heater, wherein the source supplying device supplies a metal wire as an evaporation source along a source supplying direction to a source evaporation point on the heater along a supplying direction and there is a vector from the source supplying device to the heater along the supplying direction and a projection of the vector source

Application No.: 10/692,588

Docket No.: JCLA10198

supplying direction on the plane of the substrate is parallel to overlaps with the line tangent of the circular trace at the point on the circular trace.

Claim 8. (previously presented) The evaporation apparatus of claim 7, further comprising a shelter disposed between the source supplying device and the substrate for defining an evaporation region, wherein the shelter has an opening for defining the evaporation region on the substrate.

Claim 9. (original) The evaporation apparatus of claim 8, wherein the opening is a circular opening.

Claim 10. (original) The evaporation apparatus of claim 9, wherein a radius of the evaporation region is substantially similar to that of the circular trace.

Claim 11. (original) The evaporation apparatus of claim 7, wherein the evaporation source is aluminum or silver.

Claim 12. (original) The evaporation apparatus of claim 7, wherein a rotational direction of the substrate is clockwise.

Claim 13. (original) The evaporation apparatus of claim 7, wherein a rotational direction of the substrate is counterclockwise.

Claim 14. (original) The evaporation apparatus of claim 7, wherein the heater is a rectangular loading crucible.